

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	476	dip\$4 with (etch\$3 clean\$3 wash\$3 rins\$3) with (wafer semicondcutor)	EPO; JPO; DERWENT	OR	OFF	2005/11/08 16:36
L2	114147	(rotat\$3 turn\$3 spin\$4 pivot\$4) with (hold\$3 support\$3 chuck\$3) same (slid\$3 vertical\$2 up dip\$4)	EPO; JPO; DERWENT	OR	OFF	2005/11/08 16:36
L3	1427	((rotat\$3 turn\$3 spin\$4 pivot\$4) with (hold\$3 support\$3 chuck\$3) same (slid\$3 vertical\$2 up dip\$4)) same (wafer semiconductor)	EPO; JPO; DERWENT	OR	OFF	2005/11/08 16:36
L4	790	dip\$4 with (etch\$3 clean\$3 wash\$3 rins\$3) with (wafer semiconductor)	EPO; JPO; DERWENT	OR	OFF	2005/11/08 16:36
L5	17	3 and 4	EPO; JPO; DERWENT	OR	OFF	2005/11/08 16:36